#### Low-density Start-up

D. Mueller, M. Bell, S. Gerhardt, J. Menard, R. Raman, S. Sabbagh

NSTX FY12 low density discussion: May 12, 2011

# Historically, fueling and heating help avoid MHD during start-up

- Long experience with goal of achieving long, stable, high-performance discharges has led to the present prescription
  - both low-field and high-field side gas puffing
  - Rapid Ip ramp-rate
  - Low  $I_i$  used
    - High dl<sub>p</sub>/dt
    - large aperture start-up
    - early heating
- Most of these also increase the plasma density

## New approach is needed for low density

- Simply turning off gas and/or heating does not work to produce stable plasmas
- Partial existence proof: CHI initiated discharges had low density, low I<sub>i</sub>, larger R, OH(0)=0 and were stable (but no flattop and L-Mode)
- Error fields are more likely to cause locked modes (or other MHD?) at low density (does low l<sub>i</sub> help?)
- 1. Use zero OH precharge to minimize error fields
- 2. Use high  $V_{loop}$  like CHI did
- 3. Try low voltage start-up and low  $dI_p/dt$
- 4. Use RWM coils early to correct for error fields

(In H-Mode, n<sub>e</sub>l increases about 1X10<sup>15</sup>/cm<sup>2</sup> per 0.1s)

### Strategy

- Use zero OH precharge to investigate if OHXTF is source of error fields
  - This at least starts with only eddy currents contributing to error (ramping coils, ramping errors?)
  - If this is successful, investigate error –field reduction with RWM coils next (if not try this later)
- Try high initial  $V_{loop}$ , with larger R and kappa with low gas fueling, like the low  $I_i$ , low  $n_e$  CHI shots
- Try low voltage start-up with slow dl<sub>p</sub>/dt with low gas fueling and low NBI
- Attack early error field correction
- In all cases, compare n<sub>e</sub> evolution to a 2 NB source, 700 kA fiducial plasma to evaluate success

### Zero OH pre-charge

- Starting up is straight-forward, plasma shape like fiducial
- Goal 600 or 700 kA (to have a bit of flattop)
- Use only prefill, early NBI timing like 2source fiducial
- Introduce flat spot in Ip ramp to get H-Mode
- Add some LFS gas if needed to get H-Mode
- If LFS gas does not work add some HFS gas
- Compare to same Ip, shape and gas programming, but with full OH precharge

### High loop Voltage (low early $I_i$ )

- Try about 4V/turn, about double standard
- Use lower PF5 to get larger R
- Reduce PF3/PF5 ratio like CHI case (taller plasma)
- Will require tweaking of PF1AU&L to avoid hitting top
- Make R 10cm bigger in first 70 ms
- Flattop at 600-700 kA
- Use only prefill, early NBI timing like 2 source fiducial
- Introduce flat spot in Ip ramp to get H-Mode
- Add some LFS gas if needed to get H-Mode
- Add blip of 3<sup>rd</sup> NB source
- If that does not work add some HFS

#### Low loop voltage

- During the slow ramp-up (~5 7 MA/s), we normally use ~2V/ turn for L-Mode or ~ 1.5 V/turn in H-Mode.
- Try to use <1.5 V for breakdown (will require lower prefill and PF5). Ramp to 700 kA at ~ 0.6s
- Larger plasma size at start-up generally leads to lower I<sub>i</sub>; May need this to offset the faster current penetration due to lower T<sub>e</sub> from lower input power. Start with the usual PF3/PF5 ratio and lower it as needed to get lower I<sub>i</sub>
- Use only prefill, use plasma shape similar to fiducial, but taller early on
- Inject beams early similar to 2 source fiducial
- Use usual tricks of flat-spot in Ip ramp, LFS gas, 3<sup>rd</sup> NB source, or some HFS gas to get H-Mode

### No LFS gas - early $H_{\alpha}$ spikes and higher $I_i$ , then shorter duration

